



Patent
Attorney's Docket No. 015290-457

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)

Jerome S. HUBACEK et al.)

Application No.: 09/749,916)

Filed: December 29, 2000)

For: ELECTRODE FOR PLASMA)
PROCESSES AND METHOD FOR)
MANUFACTURE AND USE)
THEREOF)

Group Art Unit: 1763

Examiner: L. L. Alejandro Mulero

Confirmation No.: 6834

#10A
8/12/02
mw

AMENDMENT

Assistant Commissioner for Patents
Washington, D.C. 20231

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Sir:

In response to the Official Action dated April 4, 2002, the period for response having been extended until August 4, 2002 by a Petition for a One Month Extension of Time submitted herewith, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel Claims 11-20 without prejudice or disclaimer of the subject matter thereof, replace Claim 1 and add new Claims 21-30 as follows:

1. (Amended) A low resistivity silicon electrode adapted to be mounted in a plasma reaction chamber used in semiconductor substrate processing, comprising:

A
B
a silicon electrode having a thickness of at least about 0.3 inch an electrical resistivity of less than 1 ohm-cm, the electrode having an RF driven or electrically grounded surface on one side thereof, the surface being exposed to plasma in the plasma reaction chamber during use of the electrode.